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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): **Annapragada et al.**

Group Art Unit: **2813**

Application Serial No.: **10/712,326**

Examiner: **Nguyen, Thanh T**

Filed: **November 12, 2003**

Title: **Minimizing the Loss of Barrier
Materials During Photoresist
Stripping**

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir/Madam:

This Amendment and Response is submitted in response to the Office Action dated May 16, 2005 in the above referenced patent application. A one-month extension is filed herewith. Please enter and consider the following amendments and remarks.

Amendments to the Claims are reflected in the listing of claims which begins on Page 2 of this paper.

Remarks begin on page 8.